





PRESS RELEASE

"PROMINENT CHINESE LAW FIRM LEADING ASIA'S LARGEST DELEGATION TO GLOBAL TRADEMARK MEETING"

Beijing – April 23, 2009 –Lehman, Lee & Xu, a top 3 China firm, has confirmed that it is leading Asia's largest delegation to the International Trademarks Association Annual meeting in Seattle, Washington, U.S.A. "INTA is one of most important events in the IP calendar" relays Ed Lehman, the firm's founder and managing director.

"I have been attending INTA since I was fourteen years old - my father was an IP attorney and our family all used to go to the event. That was 35 years ago and I still look forward to the event". The firm, which is hosting its ninth annual Brandowner's Event sees INTA as much more than a networking opportunity. "While reconnecting with old friends is one of the nicest aspects of the week; the seminars and talks on new legal developments in jurisdictions in which we have dealings is crucial to the success of our business" relays Ed.

When asked why Lehman, Lee & Xu brings such a large delegation, Ed's response is "China is one of the hottest jurisdictions for IP issues. We have a number of preeminent practitioners on our staff who are at the very forefront of legal developments here. We bring such a large delegation because each member is crucial and has his or her own area of expertise and has an essential contribtion to make. I have spent 15 years putting together the best team in China and each May we set off together. The fact that we are Asia's largest delegation is a tremendous source of pride for our firm"

Lehman, Lee & Xu is a prominent Chinese corporate law firm and trademark and patent agency with offices in Beijing, Shanghai, Shenzhen, Hong Kong, Macau, and Mongolia. The firm has been recognized as one of the top trademark firms in China by several intellectual property magazines and is managed by Mr. Edward Lehman, a leading expert on corporate law with 20 years of practice experience in Mainland China.

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